

**Amendments to the Specification:**

Please replace paragraph [0003] with the following amended paragraph:

[0003] Recently, in next generation F<sub>2</sub> resist field of vacuum ultraviolet region, there were reports on a hydroxyl-containing fluorostyrene (see T. H. Fedynyshyn, A. Cabral et al., J. Photopolym. Sci. Technol., 15, 655-666 (2002)) and on a hydroxyl-containing fluoronorbornene compound (see ~~S. Ishikawa, T. Itani et al.~~ Ralph R. Dammel, Raj Sakamuri, et al., J. Photopolym. Sci. Technol., 14, 603-612 (2001)). Thus, there was emerged an idea of containing fluorine and making polarity of hydroxyl group coexistent in the molecule. However, most compounds based on such idea have disadvantages such as too high acid strength, too low glass transition point (T<sub>g</sub>) and too low etching resistance, for example, due to their hexafluoroisopropanol (hexafluorocarbonol) structure or a secondary acid alcohol directly bonded to a cyclic fluororesin.